



IPW

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Hou, Chien-Chou; et al.)	Examiner: Deo, Duy Vu N'Guyen
)	
Serial No.: 10/600,377)	Art Unit: 1765
)	
Filed: June 20, 2003)	Our Ref: B-5130 621033-6
)	
For: "METHOD OF ETCHING UNIFORM SILICON LAYER")	Date: June 8, 2005
)	
)	Re: <i>Amendment and Response</i>
)	

AMENDMENT AND RESPONSE

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

This is in reply to the non-final Office Action mailed on March 9, 2005, an initial response to which is due no later than

June 9, 2005.

Please amend the above-identified application as described below and consider the following remarks. **All amendments and remarks herein are made without prejudice.**

Amendments to the Claims are reflected in the listing of claims that begins on page 2 of this paper.

Remarks/Arguments begin on page 5 of this paper.